

Photomask Assembly and Method for Protecting
the Same from Contaminants Generated During
Lithography Process
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FIG. 1

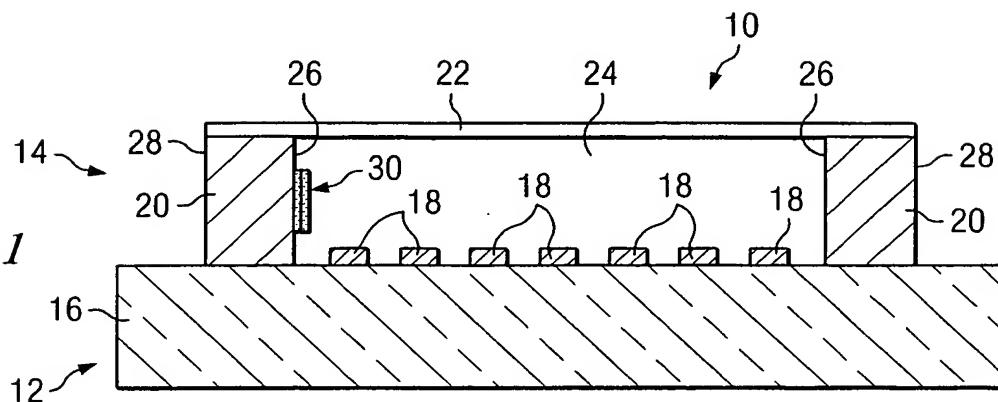


FIG. 2

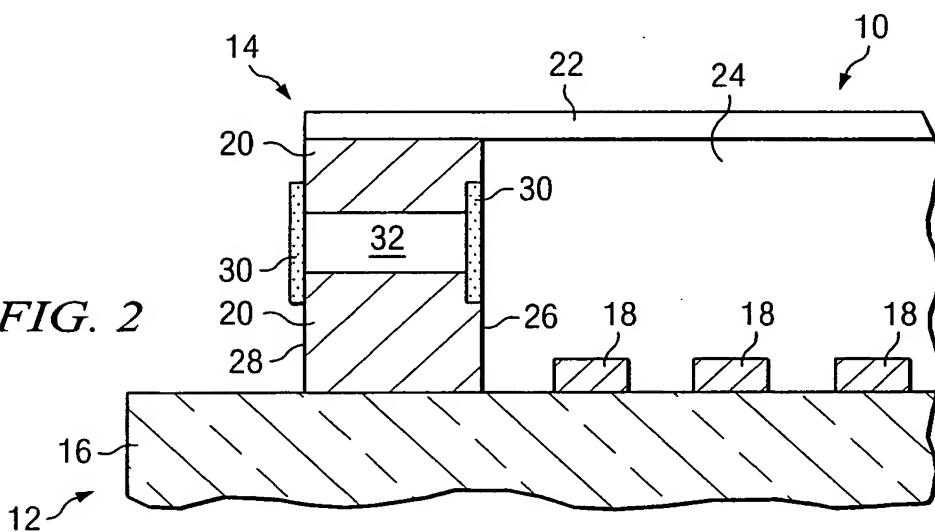
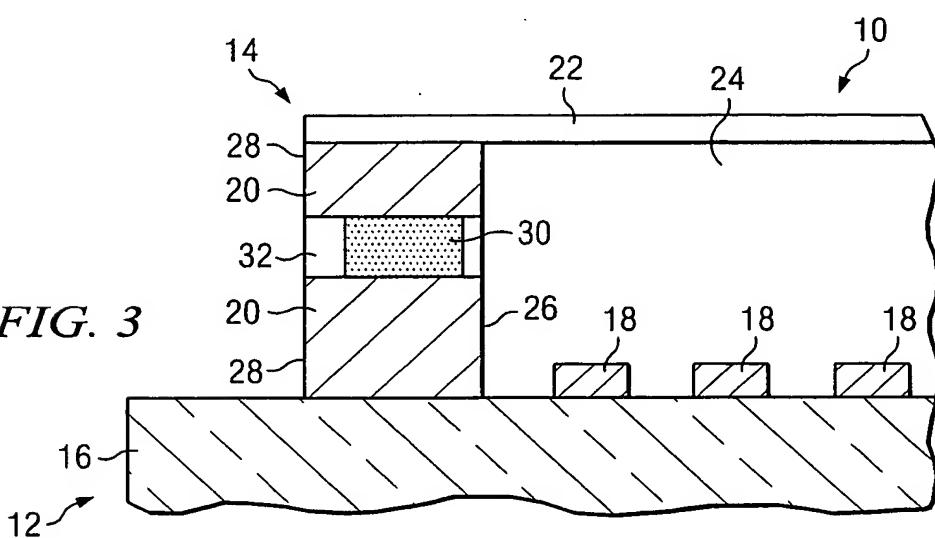


FIG. 3



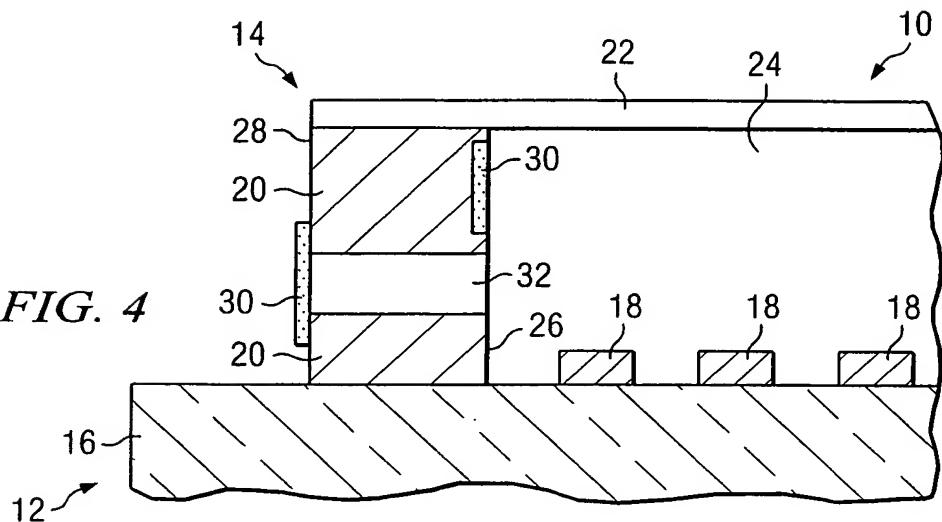


FIG. 4

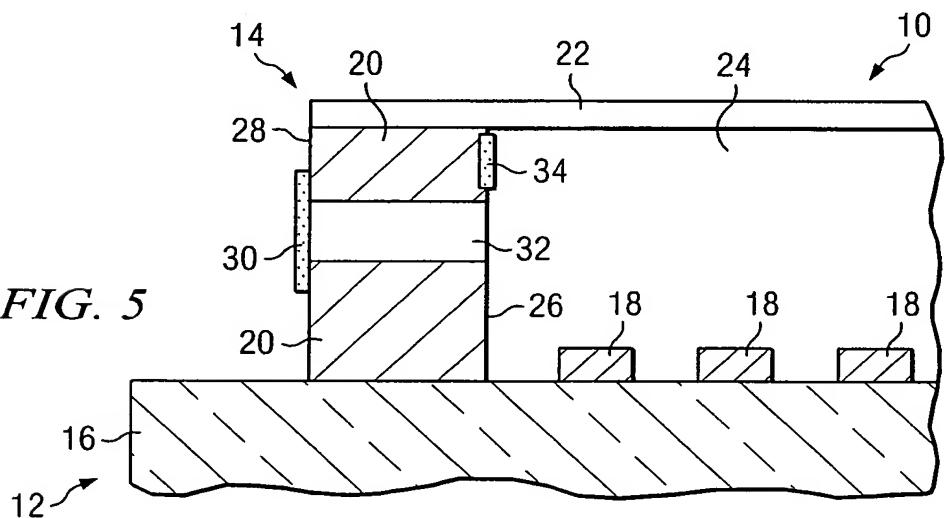


FIG. 5

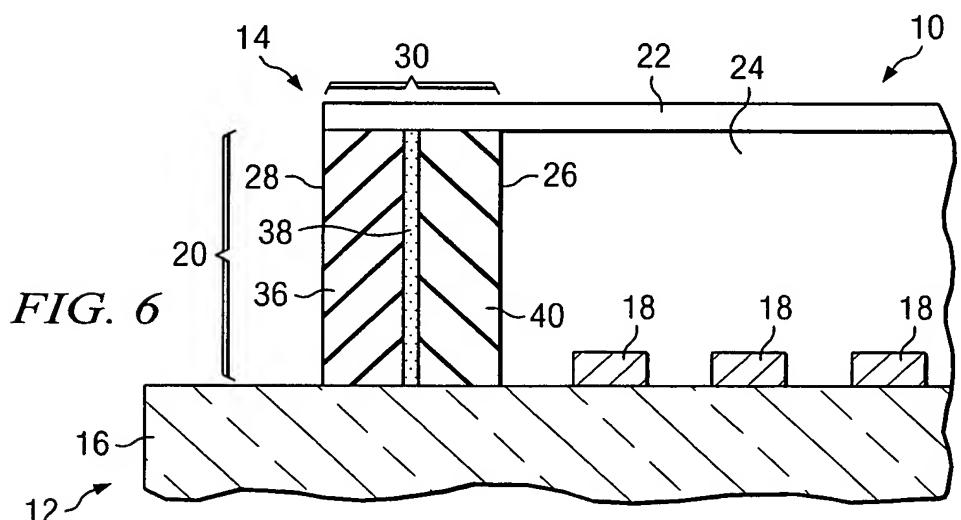


FIG. 6